1st Announcement and Call for Papers

15-17 April 2014
Pacifico Yokohama
Yokohama, Japan

Photomask Japan 2014

The 21st Symposium on Photomask and NGL Mask Technology

Symposium Chair:
Toshiyuki Horiuchi
Tokyo Denki University

Abstract Due Date:
November 15, 2013

Camera-Ready Abstract Due Date:
January 31, 2014

Manuscript Due Date:
March 13, 2014

Concrete information will be announced at the 2nd Call for Papers.

Camera-ready abstracts and manuscripts are required of all accepted applicants and must be submitted in English

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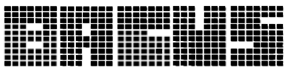

Photomask Japan 2014 is the 21st international symposium on photomasks and NGL masks in Japan. The aim of the symposium is to bring together engineers and investigators from Japan, USA, and all over the world in the field of photomasks, NGL masks, and related technologies to discuss recent progress, applications, and future trends. The conference program will feature invited papers, contributed papers, poster sessions, and a rump session with panel discussion. Display opportunities will be provided to mask manufacturing materials, and equipment companies.

Papers are solicited on the following and related topics:

- **Materials of and for Photomasks**
- **Fabrication Process Steps and Equipments for Photomasks (process and equipments for developing, etching, cleaning etc.)**
- **Photomask Writing Tools and Technologies**
- **Metrology Tools and Technologies**
- **Inspection Tools and Technologies**
- **Repairing Tools and Technologies**
- **Technologies and infrastructures for EUVL masks**
- **Mask Data Preparations, EDA and DFM**
- **Photomasks with RET: PSM, OPC, SMO and Multiple Patterning**
- **Photomask-relating Lithography Technologies**
- **NIL and masks for Patterned Media**
- **Photomasks for FPD**
- **DSA (Directed Self-Assembly)**
- **Strategies and Business Challenges: Cost, Cycle-Time, ML2 etc.**

Abstract Submissions

All authors are *strongly encouraged* to submit their abstract by the due date, November 2013 via the PMJ official website.
Abstract submission Web page will be opened from October 2013 at:

http://www.photomask-japan.org/

Further information and instruction will be available from 2nd Announcement & Call for Papers, which will be published around September, 2013

***Please do not send the abstract by e-mail or FAX.**

Conference Site

Conference site of Photomask Japan 2014 will be "Annex Hall" at Pacifico Yokohama, same as Photomask Japan 2013

For more information, contact:
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